

## IN THE SPECIFICATION

To reflect the change made to Figure 1d, the Specification should be changed to refer to the new reference number, 123. Therefore, please replace the paragraph starting on line 8 of page 14 with the following:

A1 --The process as shown in Figures 1a to 1c is repeated until, as shown in Figure 1d, the barrier layer 114 is exposed and a metal line 123 remains within the opening 112. The cerium ions in the slurry are selective in that only the material of the metal layer 116 is oxidized, and not the material of the barrier layer 114. The barrier layer 114 is thus used as a polish stop layer which prevents further removal of material.--

## IN THE CLAIMS

Presented below are the amended claims in a clean, unmarked format:

- sub D1
- A2
1. (Amended) A chemical-mechanical polishing slurry comprising:  
a liquid;  
cerium ions as an oxidizer in the liquid, the cerium ions being in a quantity equal to the inclusion of at least 0.02 molar ammonium cerium nitrate in the liquid;  
an abrasive in the liquid, the liquid, the cerium ions and the abrasive together having a first pH value; and  
a pH increasing substance in the liquid that increases the first pH value to a second pH value above 1.5 and below 3.0.

- sub D3
- A3
6. (Amended) The slurry of claim 1 wherein the pH increasing substance is glycine.